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Substitute for form 1449B/PTO			Complete if Known		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)			Application Number	09/932,239	
			Filing Date	17 August 2001	
			First Named Inventor	Christophe Pierrat	
			Group Art Unit	1756	
			Examiner Name	Mohamedulla, S.	
Sheet	1	of	3	Attorney Docket Number	NMTI 1002-3

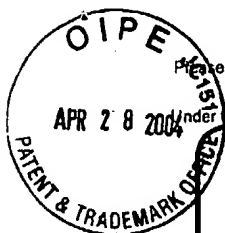
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SPM	C1	SAKATA, MIWA, et al., "A Novel Radiaion Sensitive Spin-on-glass Convertible into SiO2 and the Simple Fabrication Process Using It," 26 July 1993* (*ATI Bell Labs fax date), 3 pages.	
SPM	C2	PISTOR, THOMAS V., "Rigorous 3D Simulation of Phase Defects in Alternating Phase-Shifting Masks," Proceedings of SPIE 4562-1038 (March 2002), 13 pages	
SPM		OGAWA, KIYOSHI, et al., "Phase Defect Inspection by Differential Interference," Proceedings of SPIE 4409-71, 26 April 2001, 12 pages.	
SPM		RHYINS, P., et al., "Characterization of Quartz Etched PSM Masks for KrF Lithography at the 100 nm node," Proceedings of SPIE 4562 (March 2002), 486-495.	
SPM		SEWELL, HARRY, et al., "An Evaluation of the Dual Exposure Technique," (As early as 2002*), 11 pages *The date is based on references 8&9 of the article of 16 Feb 2001 and 27 Feb 2002, respectively.	
SPM		WANG, RUOPING, et al., "Polarized Phase Shift Mask: Concept, Design, and Potential Advantages to Photolithography Process and Physical Design," Proceedings of SPIE 4754-105, 25 April 2002, 12 pages.	
SPM		MATSUOKA, et al., "Application of Alternating Phase-Shifting Mask to 0.16um CMOS Logic Gate Patterns," SPIE Proc. 3051, March 10-14, 1997, 10 pages.	
SPM		SEMMIER, ARMIN, et al., "Application of 3D EMF Simulation for Development and Optimization of Alternating Phase Shifting Masks," Proc. of SPIE 4346-37, 1 March 2001, 12 pages.	
SPM		WONG, ALFRED K., "Polarization Effects in Mask Transmission," Proc. of SPIE 1674, 8 March 1992, 8 pages.	
SPM		ACKMANN, PAUL, et al., "Phase Shifting and Optical Proximity Corrections to improve CD control on Logic Devices in Manufacturing for sub 0.35 um I-Line," Proc. of SPIE 3051-07, March 1997, 8 pages.	
SPM		SPENCE, C., et al., "Detection of 60 degree Phase defects on Alternating PSMs," Proc. of SPIE 3412-73, April 1998, 2 pages.	

Examiner Signature	Mohamedulla	Date Considered	6/21/04
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SPM		SUGAWARA, MINORU, et al., "Defect printability study of attenuated phase-shifting masks for specifying inspection sensitivity," Proc. SPIE 2621-49, September 1995, 16 pages.	
SPM		SCHMIDT, REGINA, et al., "Impact of Coma on CD Control for Multiphase PSM Designs," Proc. SPIE 3334-02, February 1998, 11 pages.	
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SPM		GRANIK, YURI et al., "CD variation analysis technique and its application to the study of PSM mask misalignment," Proc. SPIE 4186-94, September 2000, 9 pages.	
SPM		ISHIWATA, NAOYUKI, et al., "Fabrication of Phase-Shifting Mask," Proc. SPIE 1463, March 1991, 11 pages.	
SPM		LEVENSON, MARC D., et al., "Phase Phirst! An improved strong-PSM paradigm," Proc. SPIE 4186-42, September 2000, 10 pages.	
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SPM		OZAKI, T., et al., "A 0.15um KrF Lithography for 1Gb DRAM Product using Highly Printable Patterns and Thin Resist Process," 1998 Symposium on VLSI Technology, June 1998, Honolulu, Hawaii, 2 pages.	
SPM		RONSE, KURT, et al., "Comparison of various phase shift strategies and application to 0.35 um ASIC designs," Proc. SPIE 1927, 1993, 15 pages.	
SPM		ROSENBLUTH, ALAN E., et al., "Optimum Mask and Source Patterns to Print a Given Shape," Proc. SPIE 4346-49, 1 March 2001, 17 pages.	

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STATEMENT BY APPLICANT**

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Sheet 3 of 3

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SPM		SUZUKI, AKIYOSHI, et al., "Multilevel imaging system realizing k1=0.3 lithography," Proc. SPIE 3679-36, March 1999, 13 pages.	
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SPM		TOUBLAN, OLIVIER, et al., "Phase and Transmission Errors Aware OPC Solution for PSM: Feasibility Demonstration," Proc. SPIE 4186-95, 13 September 2000, 7 pages.	
SPM		YANAGISHITA, YUICHIRO, et al., "Phase-Shifting Photolithography Applicable to Real IC Patterns," Proc. SPIE 1463, 3 March 1991, 11 pages.	
SPM		PIERRAT, C., "Investigation of Proximity Effects in Alternating Aperture Phase Shifting Masks," September 2000, 11 pages.	
SPM		COTE, MICHEL, et al., "A Practical Application of Full-Feature Alternating Phase-Shifting Technology for a Phase-Aware Standard-Cell Design Flow," 1 June 2001, 6 pages.	
SPM		HANYU, ISAMU, et al., "New phase-shifting mask with highly transparent SiO2 phase shifters," Proc. SPIE 1264-167, June 1990, pages 166-177.	
SPM		MCCALLUM, MARTIN, et al., "Alternating PSM Mask Performance - A Study of Multiple Fabrication Technique Results," Proc. SPIE 4346-723, September 2001, 6 pages.	

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